Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

- 1. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises <u>from 5 to 90 mole percent of</u> a recurring unit (1-1) shown by the following formula (I-1):

$$-CH_2-C$$
 $-CH_2-C$
 $-CH_$

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

2. (Currently Amended) The radiation-sensitive resin composition according to elaim 1, wherein the resin further comprises A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

$$-(CH_2-C)$$

$$0$$

$$(I-1)$$

$$X_1$$

$$X_2$$

$$X_2$$

$$OH$$

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-2) shown by the following formula (1-2):

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$$-CH_2-C$$
 $-CH_2-C$
 $-CH_$

wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

- 3. (Original) The radiation sensitive resin composition according to claim 2, wherein the group $-C(R_{1c})_3$ in the formula (I-2) is a l-alkyl-1-cycloalkyl group, 2-alkyl-2-adamantyl group, (1-alkyl-1-adamantyl)alkyl group, or (1-alkyl-1-norbornyl)alkyl group.
- 4. (Original) The radiation-sensitive resin composition according to claim 1, wherein the resin does not contain a lactone ring.

5. (Currently Amended) The radiation-sensitive resin composition according to elaim 4, A radiation-sensitive resin composition comprising:

(A) a resin which comprises from 5 to 90 mole percent of a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X₁ and X₂ individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator,

wherein the resin does not contain a lactone ring, and

wherein the content of the recurring unit (1-1) in the resin is 40-90 mol% in 100 mol% of the total recurring units forming the resin.

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6. (Currently Amended) The radiation-sensitive resin composition according to claim 1, wherein the resin further comprises A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-3) shown by the following formula (I-3):

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$$+CH_2$$
 $+CH_2$
 $+CH_$

wherein R_{1b} represents a hydrogen atom or a methyl group, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

- (B) a photoacid generator.
- 7. (Original) The radiation-sensitive resin composition according to claim 6, wherein the content of the recurring unit (1-1) in the resin is 5-25 mol% in 100 mol% of the total recurring units forming the resin.
- 8. (Currently Amended) The radiation-sensitive resin composition according to elaim-1, wherein the resin further comprises A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X₁ and X₂ individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-4) shown by the following formula (I-4):

$$-CH_2$$
 $-CH_2$
 $-CH_$

wherein R_{1b} represents a hydrogen atom or a methyl group, A represents a linear or branched alkyl or alkylene group having 1-4 carbon atoms or a monovalent or divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, and n is an

integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator.

- 9. (Original) The radiation-sensitive resin composition according to claim 1, further comprising (C) an acid diffusion controller.
 - 10. (New) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X₁ and X₂ individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid,

- (B) a photoacid generator, and
- (C) an acid diffusion controller.
- 11. (New) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is 1 or 2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

- (B) a photoacid generator.
- 12. (New) The radiation-sensitive resin composition according to Claim 11, wherein n is 1, 1 is 1, each X_1 is H and each X_2 is CF_3 .